Application No.: 10/705,321
Docket No.: UC0304USNA Page 2

Listing of Claims

1. (Currently Amended) A process for incorporating at least one first guest material into an organic layer comprising placing a first liquid composition over a first portion of the organic layer, wherein the first liquid composition comprises at least a first guest material and a first liquid medium, wherein the first liquid composition solvates the contact portion of the organic layer to treat the first portion of the organic layer, and a substantial amount of the first guest material migrates into the first portion of the organic layer while a second portion of the organic layer is substantially free of the first guest material, wherein the migration is performed at a temperature no greater than 40° C and in the absence of an electrical field.

- 2. (Original) The process of claim 1, wherein the organic layer is a substantially solid layer before placing the first liquid composition over the organic layer.
- (Original) The process of claim 1, wherein after placing the first liquid composition over the organic layer, substantially all of the first guest material migrates into the organic layer.
- (Currently Amended) The process of claim 3, wherein the first guest material migrates into the organic layer at [[a]] <u>substantially room</u> temperature no higher than approximately 40°C.
- (Original) The process of claim 1, further comprising forming the organic layer over a substrate, wherein placing the first liquid composition over the organic layer is performed without a well structure present over the substrate.
- 6. (Original) The process of claim 1, further comprising: forming the organic layer over a substrate; and forming a well structure over the substrate before forming the organic layer over the substrate.
- (Previously Presented) The process of claim 1, further comprising placing a second liquid composition over a second portion of the organic layer, wherein:

the second liquid composition comprises a second guest material and a second liquid medium;

the second guest material is different from the first guest material:

Application No.: 10/705,321
Docket No.: UC0304USNA Page 3

a substantial amount of the second guest material migrates into the second portion of the organic layer while a third portion of the organic layer is substantially free of the second guest material; and

a third portion of the organic layer is substantially free of the first and second guest materials.

- (Original) The process of claim 7, wherein the first liquid medium and the second liquid medium are a same solvent.
 - 9. (Canceled)

field.

10. (Original) The process of claim 1, wherein placing the first liquid composition over the organic layer is performed using a precision deposition technique.

11. (Currently Amended) A process for forming an organic layer comprising at

- least one guest material, wherein the process comprises:
 placing a first guest material over a first portion of a substrate; and
 forming the organic layer over the substrate and first guest material, wherein a
 substantial amount of the first guest material migrates into a first portion of the organic
 layer through solvation of the first portion of the organic layer, while a second portion of
 the organic layer is substantially free of the first guest material, wherein the migration is
 performed at a temperature no greater than 40° C and in the absence of an electrical
- 12. (Original) The process of claim 11, wherein after forming the organic layer, substantially all of the first guest material migrates into the organic layer.
- 13. (Previously Presented) The process of claim 11, further comprising placing a second liquid composition over a second portion of the substrate, wherein:

the second liquid composition comprises a second guest material; the second guest material is different from the first guest material; the organic layer is also formed over the second portion;

a substantial amount of the second guest material migrates into the second portion of the organic layer; and

a third portion of the organic layer is substantially free of the first and second guest materials.

14. (Canceled)

Application No.: 10/705,321

Docket No.: UC0304USNA Page 4

- 15. (Canceled)
- 16. (Canceled)
- 17. (Canceled)
- 18. (Canceled)
- 19. (Canceled)
- 20. (Canceled)
- 21. (Canceled)
- 22. (Canceled)
- 23. (Canceled)
- 24. (Canceled)
- 25. (Canceled)
- 26. (Canceled)
- 27. (Canceled)
- 28. (Canceled)
- 29. (Canceled)
- 30. (Canceled)
- 31. (Canceled)
- 32. (Canceled)
- 33. (New) The process of claim 12, wherein the migration is performed at substantially room temperature.